

Freeform Search

Database	US P Personal Bersonal	dents Full-Text Data e-Grant Publication Detracts Database Abstracts Database unt World Patents in achinical Disclosure	Full-Text Database dex	▲					
Term:									
	ay: 50 Documents in <u>Display Format</u> : - Starting with Number rate: O Hit List • Hit Count O Side by Side O Image								
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tot .	ain Menu	Show S Numbers	Edit S Numbers	Preferences	Cases	1			
Search History									

DATE: Thursday, May 23, 2002 Printable Copy Create Case



_	et Name ide by side	Query	Hit Count	Set Name result set
DΒ	USPT,PGPB,	JPAB,EPAB,DWPI,TDBD; PLUR_YES; OP_OR		
	<u>L12</u>	13 and 111	11	<u>L12</u>
	<u>L11</u>	12 near 18	51	<u>L11</u>
	<u>L10</u>	14 and 18	106	<u>L10</u>
	<u>L9</u>	14 same 18	8	<u>L9</u>
	<u>L8</u>	carboni\$4	56395	<u>L8</u>
	<u>L7</u>	14 same 15	754	<u>1.7</u>
	<u>L6</u>	14 same 15	754	<u>L6</u>
	<u>L5</u>	carbon\$5	1244473	<u>L5</u>
	<u>L4</u>	12 same 13	34669	<u>L4</u>
	<u>L3</u>	dop\$4	234222	<u>L3</u>
	<u>L2</u>	L1 adj4 (layer or film)	188814	<u>L2</u>
	<u>L1</u>	silicon or si	1336732	<u>L1</u>

END OF SEARCH HISTORY

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Print

L11: Entry 44 of 51

File: DWPI Jul 1, 1991

DERWENT-ACC-NO: 1991-234547

DERWENT-WEEK: 199132

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TITLE: Growing single-crystal silicon carbide layer on silicon wafer - by depositing silicon layer on carbonised wafer surface, and heating in hydrocarbon atmos. NoAbstract Dwg 1,2/2

PATENT-ASSIGNEE: FUJITSU LTD (FUIT)

PRIORITY-DATA: 1989JP-0292903 (November 10, 1989)

PATENT-FAMILY:

PUB-NO PUB-DATE LANGUAGE PAGES MAIN-IPC

JP 03153023 A July 1, 1991 000

APPLICATION-DATA:

DESCRIPTOR PUB-NO APPL-DATE APPL-NO

JP03153023A November 10, 1989 1989JP-0292903

INT-CL (IPC): H01L 21/20

DERWENT-CLASS: L03 U11

CPI-CODES: L04-A; L04-A01; L04-C16;

EPI-CODES: U11-C01A9; U11-C01J4; U11-C03J7;

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